

Creating value for customers

FEOL photo track technology: latest trends and development

Xinglong Chen, CTO, Kingsemi

www.kingsemi.com

2018/2

Domestic FEOL photo track market

为客户创造价值





- China fab boom brings domestic equipment market to over \$10 Billions in 2018
- Photo track equipment market will grow with it, what is there for domestic suppliers?

Photo track technology trends

为客户创造价值

www.kingsemi.com

Node shrinkage and productivity/yield requirement continue to drive photo track technology improvement

- Faster higher throughput follows photolithography tool improvement
- Cleaner more stringent spec for defects/PC
- Flatter tighter WIW uniformity and edge excursion
- More tolerable adapt to large wafer warpage
- Smarter self diagnostics and self calibration
- Friendlier more intuitive user-interface, easier PM process

In the light of these ever challenging requirements, what are domestic suppliers doing?

www.kingsemi.com

KingSemi Profile

- Founded and headquartered in 2002 at Shenyang with branches at Shanghai, Guangzhou, and Taiwan
- Leading domestic photo track company, led photo track projects of national 11th and 12th 5-year plan
- Serviced markets: photo track for LED, bumping, advanced packaging and FEOL
- Fully-equipped R&D labs for hardware design and process verification
- In-house manufacturing capability
- More than 200 employees, annual sales of 200M RMB with annual growth rate >20%
- IP portfolio includes over 300 patents in China and US





KingSemi Profile

- Coater/developer portfolio and serviced markets

为客户创造价值



Kingsemi FEOL photolithography track

- Technology roadmap



为客户创造价值

www.kingsemi.com

Based on a fully extendable platform, Kingsemi photo track products will cover KrF, I-line, immersion and beyond

Kingsemi photolithography track



Kingsemi FEOL photo track has been developed for volume production for logic and memory customers.

- Designed from ground up, based on learnings from 02 special R&D program, focusing in improvements for yield and productivity
- Supports mainstream photolithography technologies, including BARC, ArF, KrF and I-line
- Flexibility to operate in-line or off-line
- Alpha-phase equipment has finished marathon test; Betaphase equipment to be deployed to multiple major fabs in China
- Throughput up to 240 WPH



为客户创造价值



Kingsemi photolithography track - Hardware features and innovations



			Productivity	Defects	Performance	CoO
Category	Item	Design feature				
Coater	Chemical delivery	Chemical automatic recirculation				
		Real-time dispense monitoring				
		Multi-nozzle arm to reduce overhead time				
		Automatic nozzle clean and segmented suckback function		\checkmark	\checkmark	\checkmark
		CFD-optimized cup design and new material				
Baker	Temperature control	Integrated cooling and heating plate with high speed drive				
	New heater design	Multi-zone distributed heating for temperature uniformity	\checkmark		\checkmark	
	HMDS chamber	CFD-optimized aerodynamic design				
Platform	Transfer robot	High-speed precision robot that enables 300Wph throughput	\checkmark	\checkmark		\checkmark
	Wafer holding mechanism	Adaptive vacuum pads to avoid bevel contact			\checkmark	

Kingsemi photolithography track

Operator-friendly GUI, intuitive and easy to use

- Main window with all unit overview
- Easy to use recipe editor
- One-click routines, such as dummy run and cup clean
- Full-functionality manual mode
- Full-equipment data logging capabilities
 - All operations from GUI recorded; Alarm database stores all alarm events for over 6 months
 - Job database records all lot related information
 - Support FDC and customized SVID integration
 - Smart self-diagnostics functionalities

Security – user access level specific GUI

为客户创造价值



Kingsemi photolithography track



Application 1 – BARC film (customer A)

- Thickness spec: 750Å, OOC:±12Å; OOS:±18Å
- Uniformity spec: OOC:20Å; OOS:25Å
- Met spec for 60 days continuous production



为客户创造价值





沈阳芯源微电子设备有限公司

地址: 沈阳市浑南新区飞云路16号 邮编: 110168 电话: (86-24)2382-6255 传真: (86-24)2382-6200

